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First Named Inventor Ryza et al.

Group Art Unit 4223 1756

Examiner Name Unknown DUDA

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Attorney Docket Number TEX1100

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U.S. PATENT DOCUMENTS

Examiner Initials	Cite No.	Document Number		Kind Code (if known)	Publication Date MM-DD-YYYY	Name of Patentee or Applicant of Cited Document
		Number	Class/Int			
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Examiner Signature	K. Duda				Date Considered	12-8-03



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ICAD	B3	EP	0 397 826	B1	12/16/92	Hughes Aircraft Company
	B4	JP	60 192333	A	9/30/85	Hitachi Selsakusho

OTHER PRIOR ART -- NON PATENT LITERATURE DOCUMENTS

Examiner Initials	Cite No.	Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city and/or country where published.	Date
KAD	C1	KING, et al., "The Mutual Solubilities of Water with Supercritical and Liquid Carbon Dioxide", The Journal of Supercritical Fluids, Volume 5, pages 296-302.	May 1992
ICAD	C2	PERRY, et al., "Chemical Engineers' Handbook", 5th Edition, pp. 21-11 to 21-14 (4 sheets).	1973
ICAD	C3	Phase Diagram for CO ₂ as found at http://www.chem.uncc.edu/faculty/murphy/1252/Chapter11B/sldoo4.htm	February 7, 2002
ICAD	C4	Bruan, et al., "Photostrip faces 300 nm, copper and low-k convergence," 7 pages, Semiconductor International.	September 2000
ICAD	C5	Sundararajan, et al., "Block copolymers as supercritical CO ₂ developable photoresists" Department of Materials Science and Engineering, pp. 130-131.	--
ICAD	C6	Rubin, et al., "A Comparison of Chilled DI Water/Ozone and CO ₂ -Based Supercritical Fluids as Replacements for Photoresist-Stripping Solvents," International Electronics Manufacturing Technology Symposium, pp. 308-314.	January 1998
ICAD	C7	Gabor, et al., "Block and Random Copolymer Resist Designed for 193 nm Lithography and Environmentally Friendly Supercritical CO ₂ Development," SPIE Vol. 2724, pp. 410-417.	June 1996
ICAD	C8	Wetmore, et al., "Supercritical Fluid Processing: A New Dry Technique for Photoresist Developing," SPIE Vol. 2438, pp. 694-703.	June 1995
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